What is claimed is :

1. A method of manufacturing a polishing pad, the method comprising:

(a) producing an urethane prepolymer having a viscosity of 20,000 cps (at 25℃) to 40,000 cps (at 25℃) greater than the viscosity of a plurality polymer molecules by mixing the plurality of polymer molecules;

(b) mixing the urethane prepolymer produced at the producing step (a) with an inert gas and a low-boiling blowing agent having a boiling point of 60℃ to 150℃; and

(c) manufacturing a polishing layer including porous pores by causing a mixture produced at the mixing step (b) to be subjected to gelation and curing in a predetermined cast,

wherein, the mixing step (b) includes causing an average size of pores produced by mixing the inert gas of 5% to 30% and the low-boiling blowing agent of 0.1% to 10% of a total volume of a mixture produced at the mixing step (b) with the urethane prepolymer produced at the producing step (a) to be 31 μm or smaller.

2. The method according to claim 1, wherein,

the producing step (a) includes producing the urethane prepolymer by mixing a polymer having tetravalent or more hydroxyl group, and

the manufacturing step (c) includes manufacturing the polishing layer with a generation of a glazing phenomenon suppressed by forming a

polyurethane having a three-dimensional bonding structure by mixing the urethane prepolymer produced at the producing step (a) and a curing agent.

3. The method according to claim 2, wherein, the plurality of polymer molecules includes any one selected from the group consisting of polypropylene glycol, polyurethane, polyether, polyester, polysulfone, polyacrylic, polycarbonate, polyethylene, polymethyl methacrylate, polyvinyl acetate, polyvinyl chloride, polyethyleneimine, polyethersulfone, polyetherimides, polyketone, melamine, nylon, fluorohydrocarbon, and any combination thereof.

4. The method according to claim 2, wherein, the polymer having tetravalent or more hydroxyl group is included by a content of 1% to 30% of a weight of the urethane prepolymer produced at the producing step (a).

5. The method according to claim 1, further comprising spreading pores from opening the porous pores on a surface of the polishing layer by processing the polishing layer.